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L2	1	1 and alkaline	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:08
L3	2	1 and (dissolution with rate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:09
L4	359	alkaline with (dissolution adj rate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:09
L5	1	4 and (spatial with average)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:10
L6	6	4 and spatial	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:10
L7	8	("5379225" | "5434440" | "5745388").PN. OR ("5889686").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/11/22 14:35
L8	1732	((703/6) or (716/19,21)).CCLS.	USPAT	OR	OFF	2006/11/22 14:35
L9	52	8 and (photosensitive with resist)	USPAT	OR	OFF	2006/11/22 14:39
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